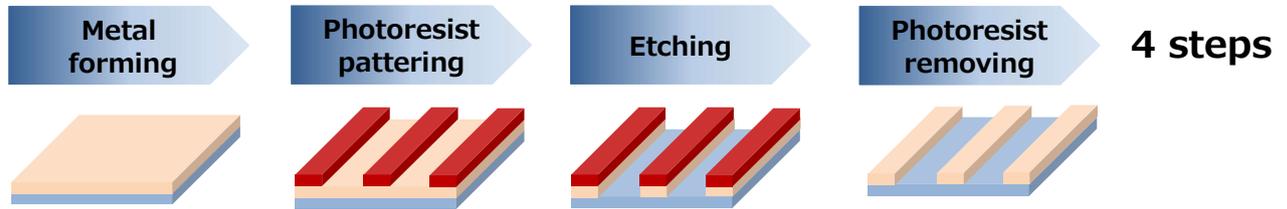


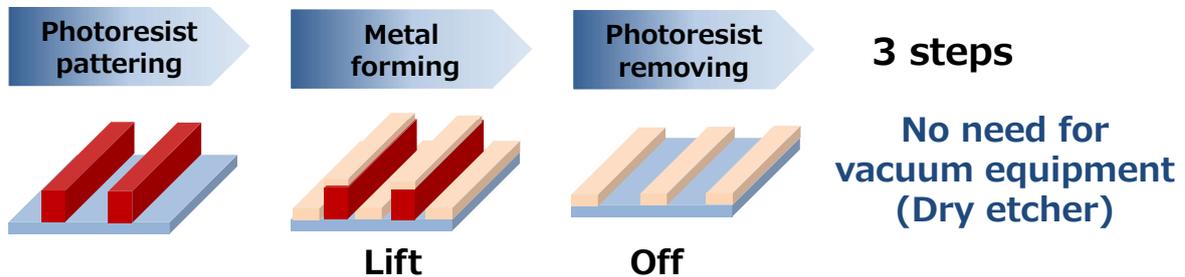
# NAGASE Photoresist for Lift-off Process

## Lift-off Process

Etching process ( Conventional )



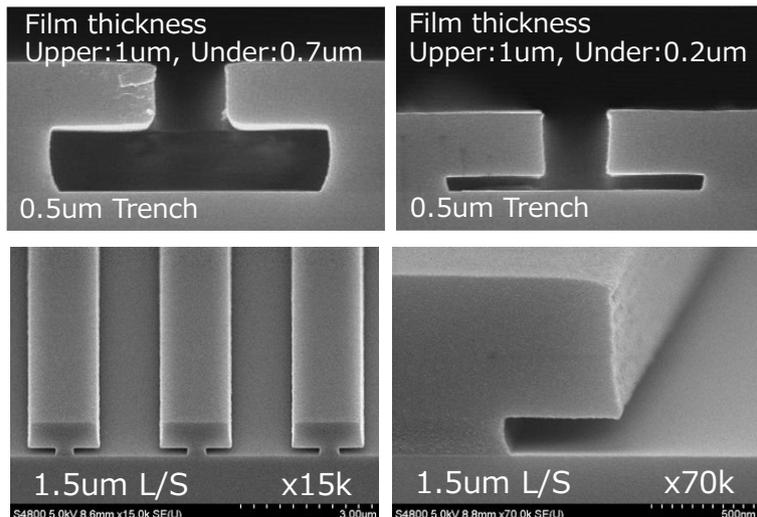
Lift-off process



## Product by i-line stepper exposure (NA=0.45)

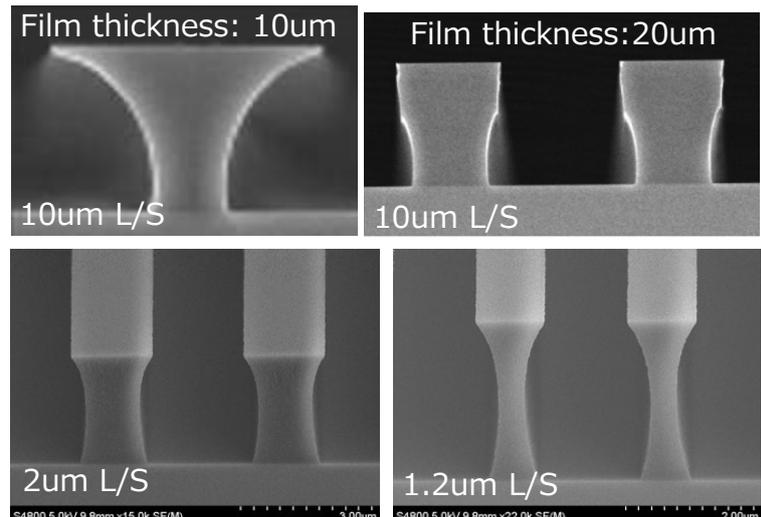
Bi-layer type

**BLX series ( Under layer )**



Single-layer type

**NPR9700 series**



- No intermixing
- Applicable to various upper layer
- Selectable of exposure wavelength depending on upper layer

- Positive-tone type
- Simple process
- Good step coverage
- Suitable anti-tapered profile

**Customizable for customer needs**